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Please cancel claims 15, and 16.

Please amend claims 21 and 24 as follows:

E 3
1 ~~21~~. (Amended) A method for manufacturing a filter medium for an air filter to be used in the manufacture environment of a semiconductor device, comprising the steps of forming a non-woven fabric by binding fibers by a binder, said binder having its chief ingredient of a polymer dispersion having a copolymer of a hydrophilic monomer and a hydrophobic monomer dispersed in water, and

obtaining said polymer dispersion [obtained] by a polymerization step of dissolving the hydrophilic monomer in water, adding the hydrophilic monomer to this water solution and dispersing said hydrophobic monomer in said water solution, and adding a polymerization initiator to form said copolymer,

wherein in said polymerization step, a hydrophilic organic peroxide of cumen hydroperoxide, 2, 5-dimethylhexan-2, 5-hydroperoxide, or succinic acid peroxide is used as a polymerization initiator.

E 4
claim 21 ~~21~~ ² 24. (Amended) A filter medium manufactured by the method of

Please cancel claims 25, 28, and 30.

Please amend claim 31 as follows:

E 5
3 ~~31~~. (Amended) Local clean equipment having an air filter according to claim 27 installed therein.

Please cancel claims 32, 33, and 34.

Please amend claim 35 as follows:

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E 5 ~~63~~. (Amended) A method for manufacturing semiconductors,
wherein a silicon wafer for said semiconductor is processed in at least one of a clean
room and local clean equipment having an air filter as defined in claim ~~27~~ 3

Please cancel claim 36.

Please amend claim 37 as follows:

E 7 ~~37~~. (Amended) A semiconductor device made by processing a
silicon wafer in at least one of a clean room and local clean equipment having an air
filter as defined in claim ~~27~~ 3

Please cancel claim 38.